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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	. ATTORNEY DOCKET NO.	CONFIRMATION NO.		
10/675,996	10/02/2003	Hiroyuki Koide	00862.023261.	7786		
5514 7	7590 04/20/2005		EXAM	EXAMINER		
FITZPATRICK CELLA HARPER & SCINTO 30 ROCKEFELLER PLAZA			JONES, J	JONES, JUDSON		
NEW YORK,			ART UNIT	PAPER NUMBER		
			2834			
			DATE MAILED: 04/20/200	5		

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	γ.
	10/675,996	KOIDE, HIROYUKI	
Office Action Summary	Examiner	Art Unit	
	Judson H. Jones	2834	
The MAILING DATE of this communication Period for Reply	n appears on the cover sheet w	ith the correspondence address	5
A SHORTENED STATUTORY PERIOD FOR R THE MAILING DATE OF THIS COMMUNICATI  - Extensions of time may be available under the provisions of 37 C after SIX (6) MONTHS from the mailing date of this communicatio  - If the period for reply specified above is less than thirty (30) days, - If NO period for reply is specified above, the maximum statutory p - Failure to reply within the set or extended period for reply will, by Any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1.704(b).	ON. FR 1.136(a). In no event, however, may a ron. a reply within the statutory minimum of thir period will apply and will expire SIX (6) MON statute, cause the application to become Al	reply be timely filed  ty (30) days will be considered timely.  ITHS from the mailing date of this commun  BANDONED (35 U.S.C. § 133).	ication.
Status			
1) Responsive to communication(s) filed on			
	This action is non-final.		
3) Since this application is in condition for al	•	ers, prosecution as to the mer	its is
closed in accordance with the practice un	der <i>Ex parte Quayl</i> e, 1935 C.D	). 11, 453 O.G. 213.	
Disposition of Claims			
4) ⊠ Claim(s) <u>1-10</u> is/are pending in the applic 4a) Of the above claim(s) is/are wit 5) ☐ Claim(s) is/are allowed. 6) ⊠ Claim(s) <u>1,2,6 and 8-10</u> is/are rejected. 7) ⊠ Claim(s) <u>3-5 and 7</u> is/are objected to. 8) ☐ Claim(s) are subject to restriction a	hdrawn from consideration.	,	
Application Papers			
9)☐ The specification is objected to by the Exa  10)☒ The drawing(s) filed on <u>02 October 2003</u> is  Applicant may not request that any objection to  Replacement drawing sheet(s) including the color of the properties of the prop	s/are: a)⊠ accepted or b)⊡ c o the drawing(s) be held in abeyal orrection is required if the drawing	nce. See 37 CFR 1.85(a). (s) is objected to. See 37 CFR 1.	` .
Priority under 35 U.S.C. § 119			
12) △ Acknowledgment is made of a claim for fo a) △ All b) ☐ Some * c) ☐ None of:  1. △ Certified copies of the priority docu 2. ☐ Certified copies of the priority docu 3. ☐ Copies of the certified copies of the application from the International B  * See the attached detailed Office action for	ments have been received. ments have been received in A priority documents have been ureau (PCT Rule 17.2(a)).	Application No  received in this National Stag	e
Attachment(s)	<b></b>		
<ol> <li>Notice of References Cited (PTO-892)</li> <li>D Notice of Draftsperson's Patent Drawing Review (PTO-94</li> </ol>	4) ☐ Interview 9 8) Paper No(	Summary (PTO-413) s)/Mail Date	
3) Information Disclosure Statement(s) (PTO-1449 or PTO/S Paper No(s)/Mail Date		nformal Patent Application (PTO-152)	)

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#### **DETAILED ACTION**

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 2, 6 and 8 are rejected under 35 U.S.C. 102(b) as being anticipated by Novak et al. 5,623,853. Novak et al. discloses a first Y direction actuator having a stator 20 and a movable element 22b wherein the stator is driven by a second X direction actuator in a direction to suppress rotation of the stator 20 as described in Novak et al. column 16 lines 8-24.

In regard to claim 2, see Novak et al. column 15 lines 59-64.

In regard to claim 6, see Novak et al. column 15 lines 59-64 and see column 15 lines 28-36. The manipulated variable is the output of the position measuring system.

In regard to claim 8, the reaction force is the force that cause stator 20 to yaw. When linear motors 110a, 110b are driven to counteract the yaw, they cause the stator to absorb the reaction force.

### Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claims 9 and 10 rejected under 35 U.S.C. 103(a) as being unpatentable over Novak et al. in view of Nishi 6,396,568 B1. Novak et al. teaches that his device is for microlithography in column 1 lines 12 and 13 and discloses exposure in column 1 line 20. The additional details present in claims 9 and 10 such as applying a photosensitive material onto a resist and using an optical system to irradiate the photosensitive material are details of a microlithography system. See Nishi column 1 lines 7 ½ -12 ½ where a general description of a photolithography process is given. Photolithography for semiconductors is what Novak et al. is calling microlithography. Instead of using the word "master" used by applicant in claim 9, Nishi mentions transferring a mask pattern. The mask pattern is the master. Nishi mentions "a photosensitive substrate" in lines 8 and 9 of column 1 and mentions "photoresist coated on wafer (W)" in column 1 line 36 1/2. In column 1 lines 15 1/2 to 19 1/2 Nishi states that the wafer coated with photoresist forms the photosensitive substrate. The step of applying a photosensitive material on a substrate is implied in the Nishi reference and is inherent. The developing step present in applicant's claim 10 is mentioned in Nishi column 1 38 ½ to 40 ½. Nishi does not use the word "irradiate." Nishi states "exposes the photoresist coated on wafer (W) under the illumination light." This exposure is the irradiation step. Since Nishi and Novak et al. are from the same field of endeavor it would have been obvious at the time the invention was made for one of ordinary skill in the art to have utilized Nishi to supply details on the microlithography method that were not provided in Novak et al.

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#### Allowable Subject Matter

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Claims 3-5 and 7 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The following is a statement of reasons for the indication of allowable subject matter:

The prior art of record does not disclose or teach controlling a second actuator on the basis of acceleration of a movable element as recited in claim 3. Novak et al. mentions acceleration in column 10 lines 55-58 and states that the counter force from acceleration of the movable element 22b is not transferred to the beam 20 (the stator of the first actuator). Thus Novak et al. does not control the second actuator on the basis of acceleration. The prior art of record does not disclose or teach anything about the barycenter of the stator in combination with the other features of claim 7.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Shiraishi 5,335,044 teaches 4 different exposure methods, with the barycenter being a part of the 4<sup>th</sup> method. Pastor 6,279,490 B1 shows a first actuator 10 and a second actuator 8 with the stator of 1<sup>st</sup> actuator driven by the second actuator. Pastor is concerned with yaw but in the Pastor device element 12 is rotated to counter-act yaw.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Judson H. Jones whose telephone number is 571-272-2025. The examiner can normally be reached on 8-4:30 M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Darren Schuberg can be reached on 571-272-2044. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Judson Jones 4/13/2005

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